

# Gain enhancements of CO<sub>2</sub> laser amplifiers by using transverse-gas-flow configuration to boost up driving powers for EUV generations

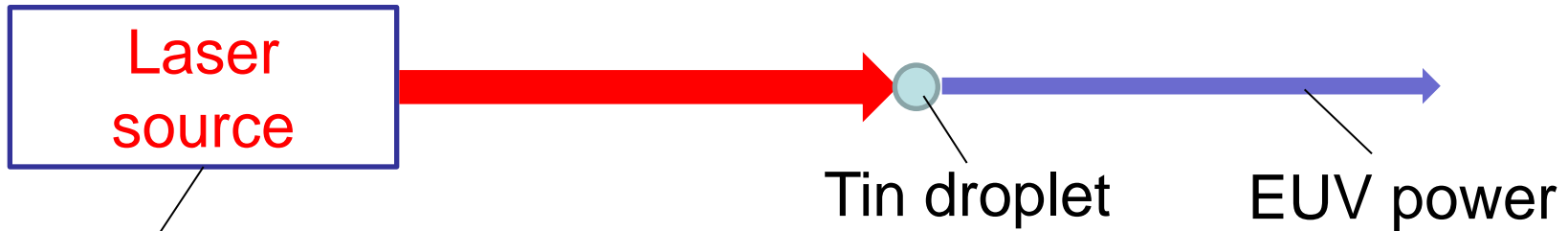
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## - EUV lithography fields -

1. Not enough EUV powers achieved so far.
2. Stable EUV apparatus required for real business.
  - (1) Physical stability
  - (2) Business capability



## Requirements

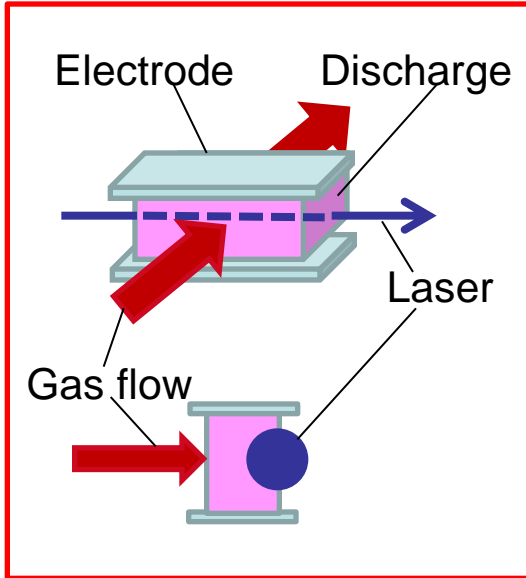
1. Enough driving powers
2. Physical stability
3. Business capability

## Transverse-gas-flow CO<sub>2</sub> lasers

- ← Higher amplifier gains
- ← Lower gas-flow speed
- ← Cutting capability



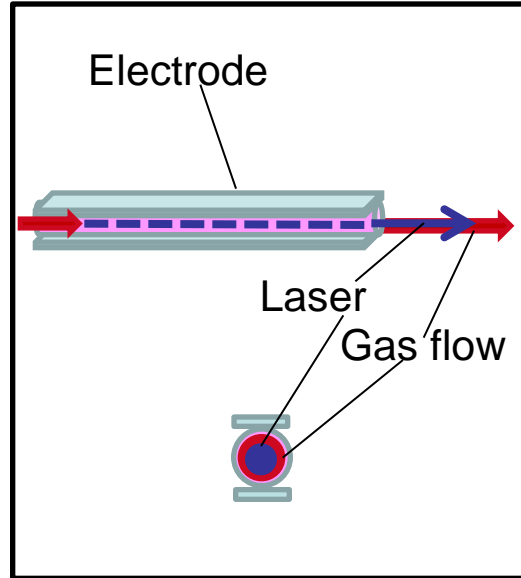
## Transverse-gas-flow CO<sub>2</sub> lasers vs. other CO<sub>2</sub> lasers



### 1. Transvers-gas-flow

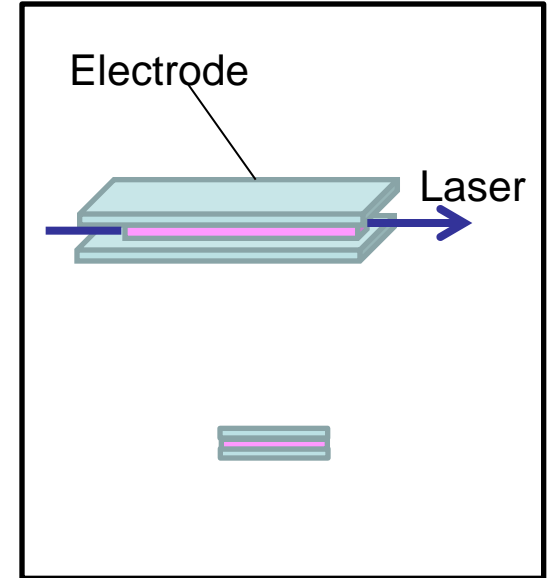
Low flow  
 +Short length  
 ⇒Stable operation

Higher gain  
 ⇒Higher power



### 2. Fast-axial-flow

Fast flow  
 Long length

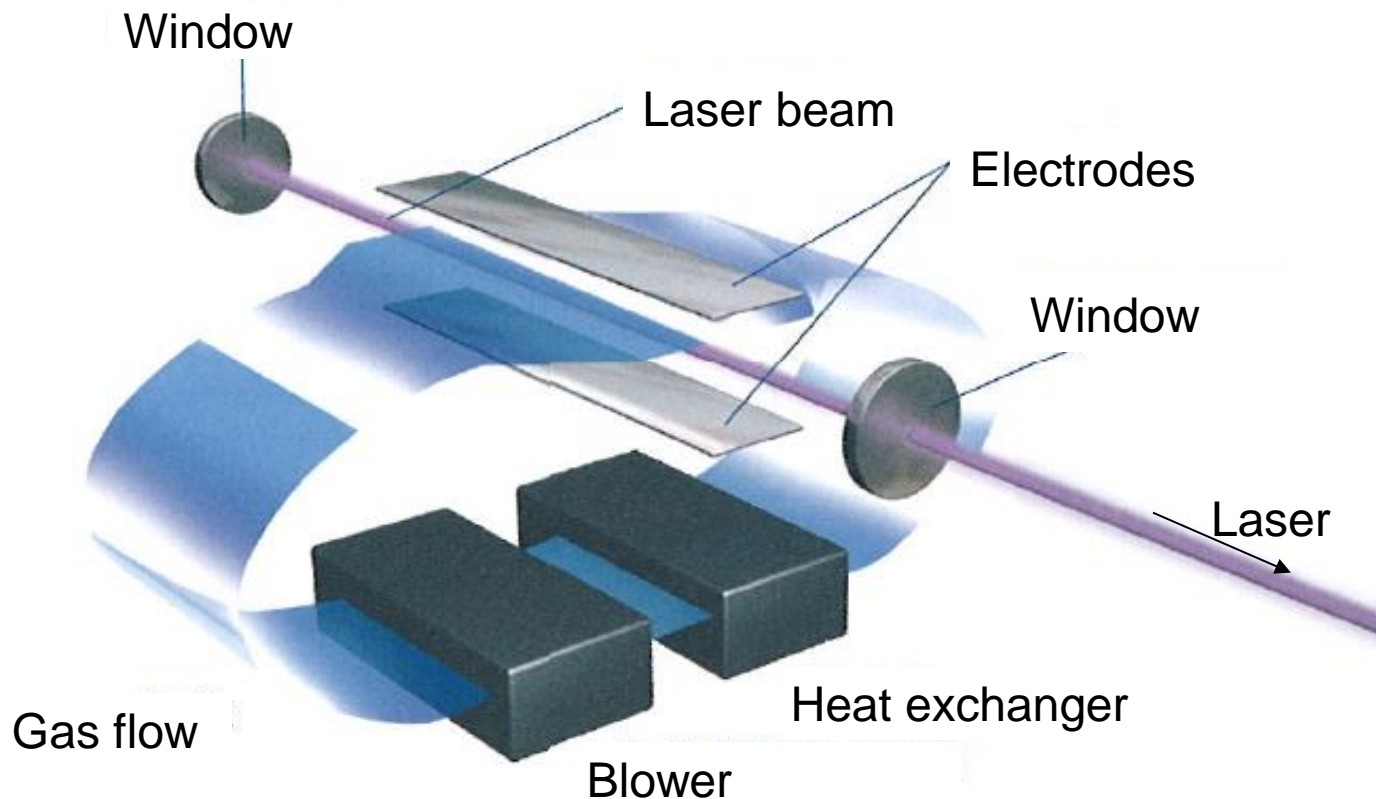


### 3. No flow

No flow  
 Wide area

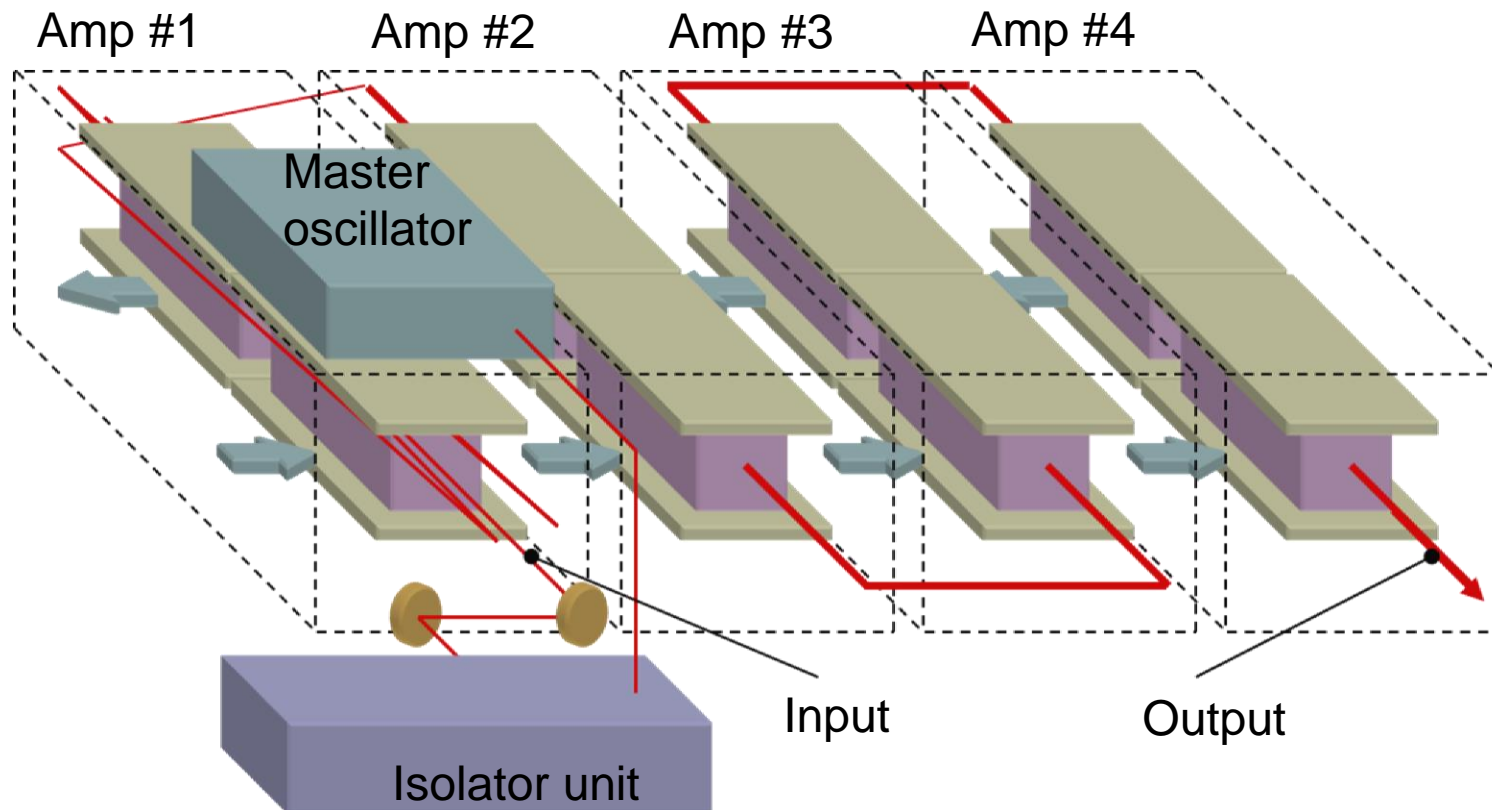
## Transverse-gas-flow CO<sub>2</sub> laser

- Gas flow is flowing transversely to the laser beams

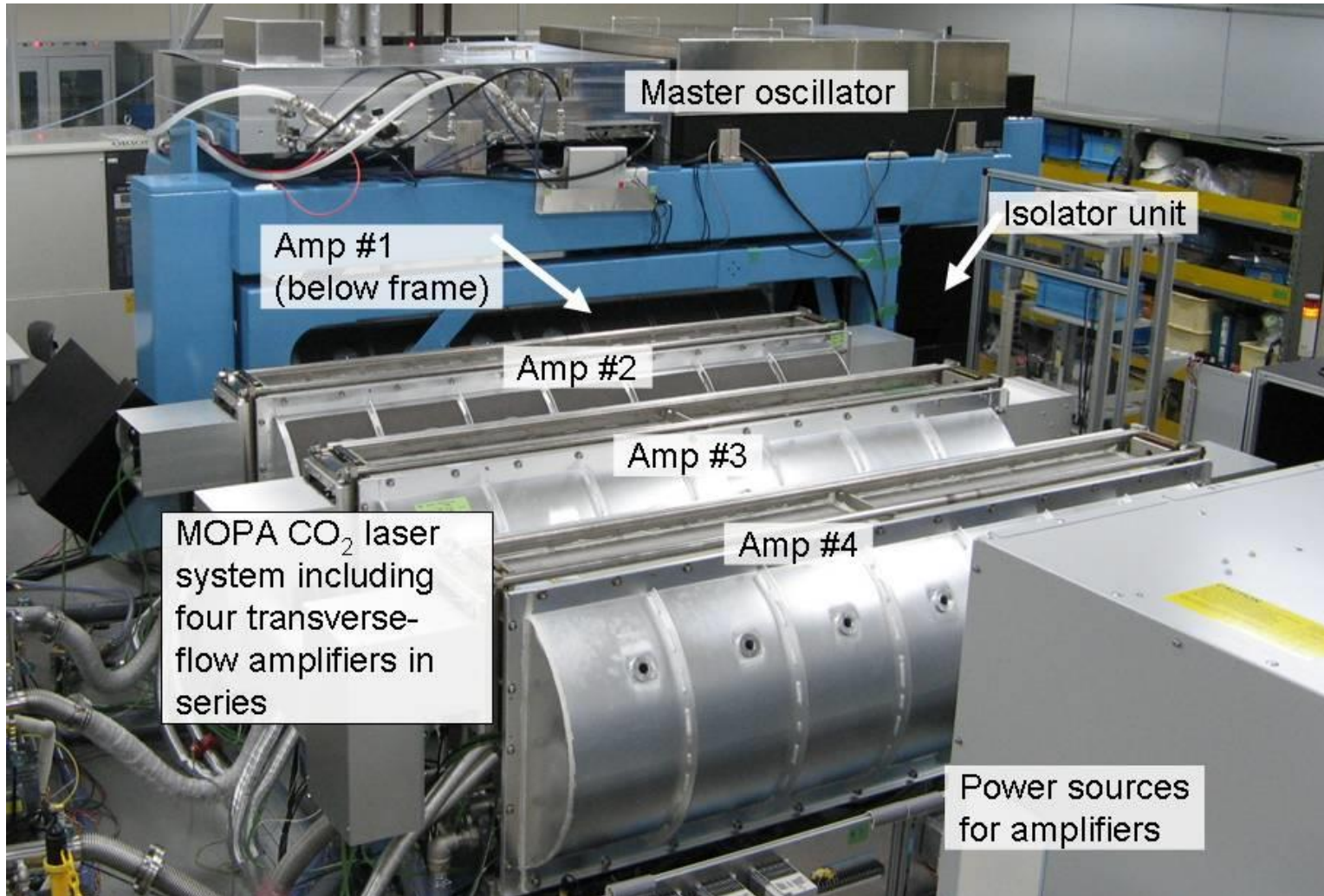


### Over view

- Four transverse-gas-flow amplifiers
  - Five-folded optical path in amp #1
  - Straight paths in amp #2,#3,#4

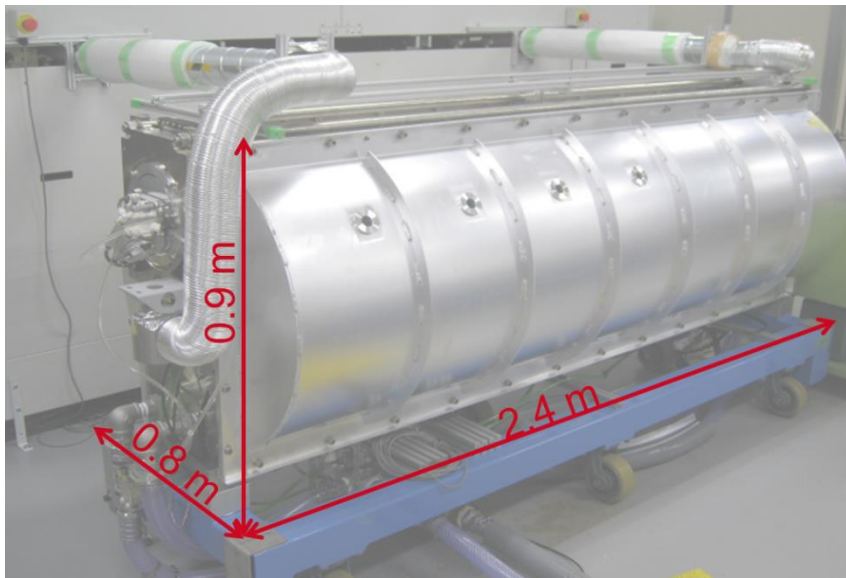


### Over view



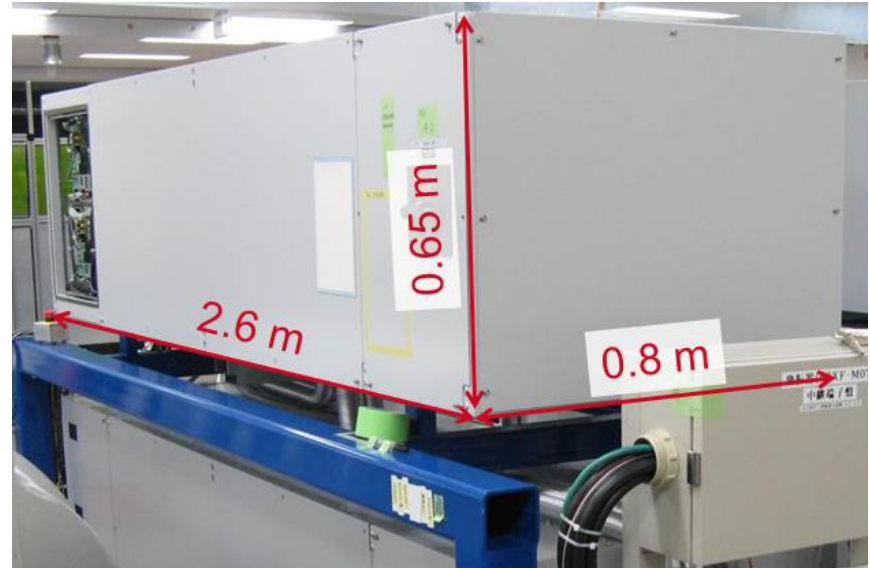
### Amplifier

L2.4m H 0.9m W 0.8m



### Power source

L2.6m H 0.65m W 0.8m



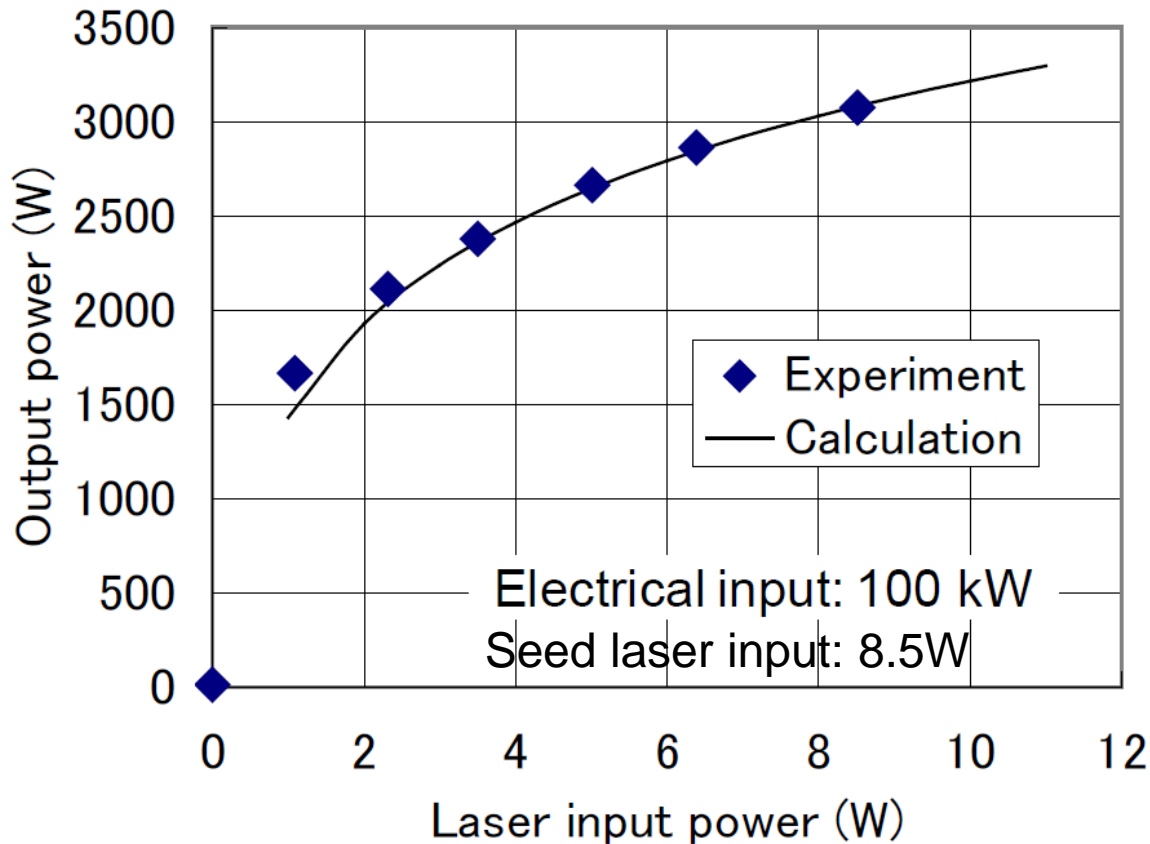


## Operating conditions

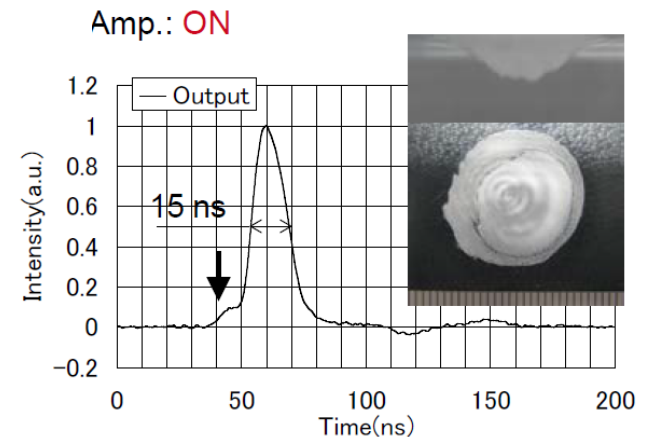
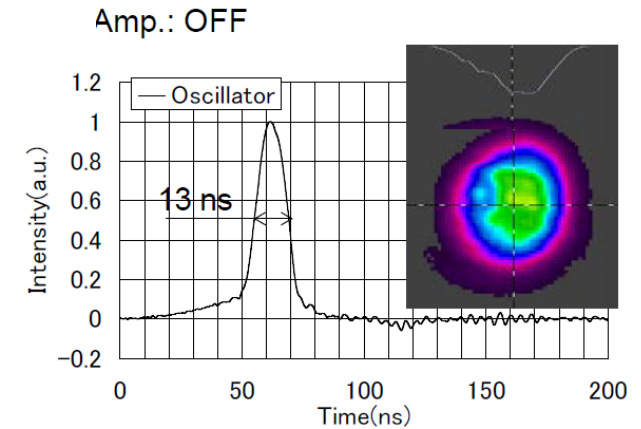
- Electrical input powers for discharge: 100 kW x4, duty 33%
- Laser input: 15 ns, 100 kHz

Master Oscillator	
Wavelength	10.6 $\mu\text{m}$ P(20,22)
Repetition frequency	100 kHz
Pulse duration	15 ns
Amplifiers	
Laser input	22 W max
Beam radius( $1/e^2$ )	6 mm@amp#1 , 15 mm@amp#2-4
Electrical input	100 kW max x4
Discharge duty	33%
Discharge volume	5x4x188 $\text{cm}^3$ x4
Gas pressure	7.0 kPa

## Single amplifier performance

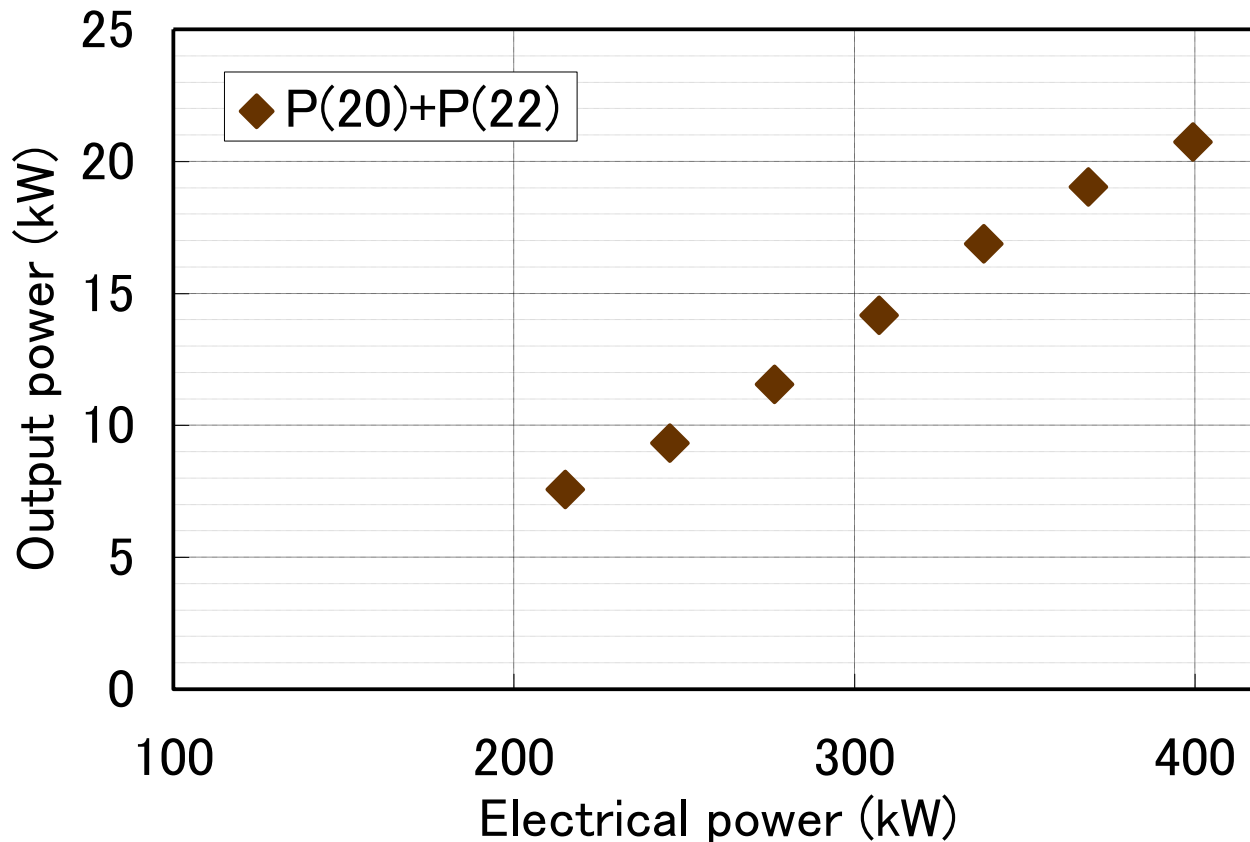


## Amp #1 Waveform and Beam pattern

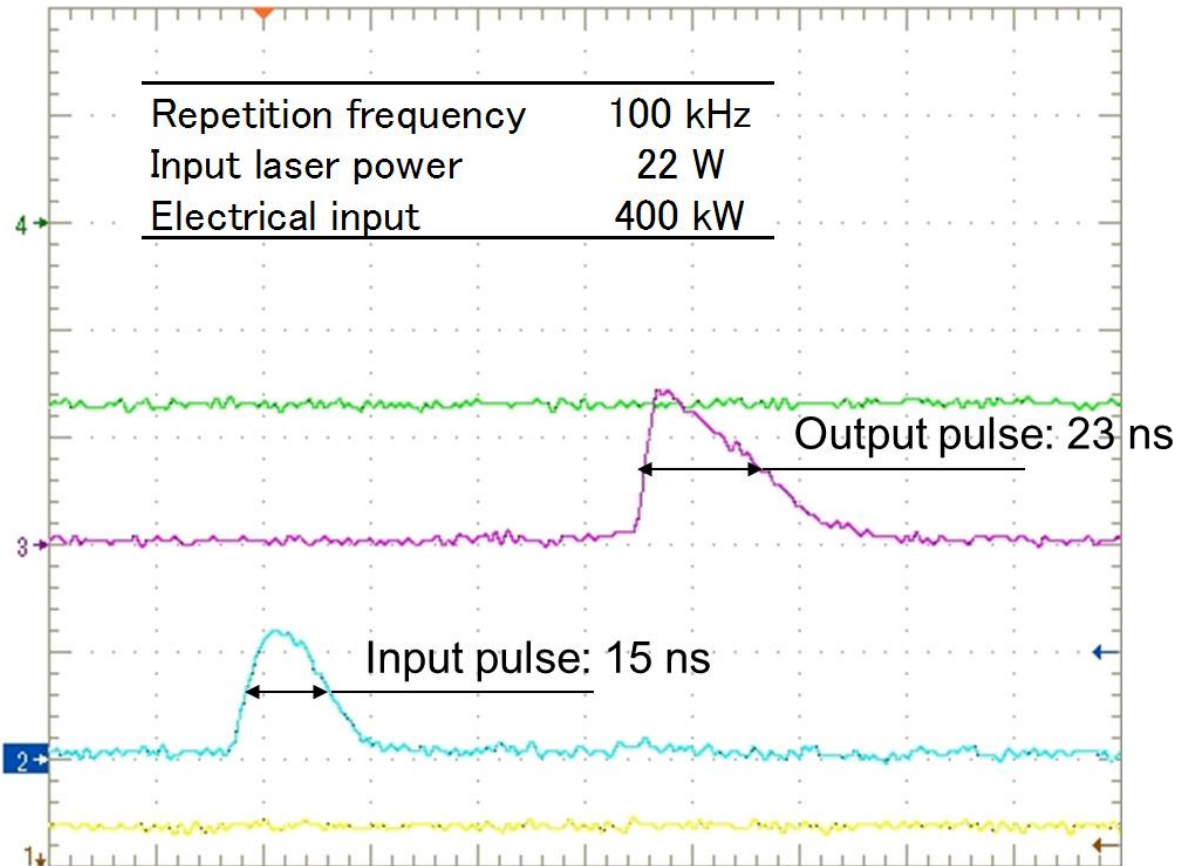


## Four amplifiers driven by two-line oscillator

- Output power **21 kW** was demonstrated (duty 33%)



## Pulse shape example

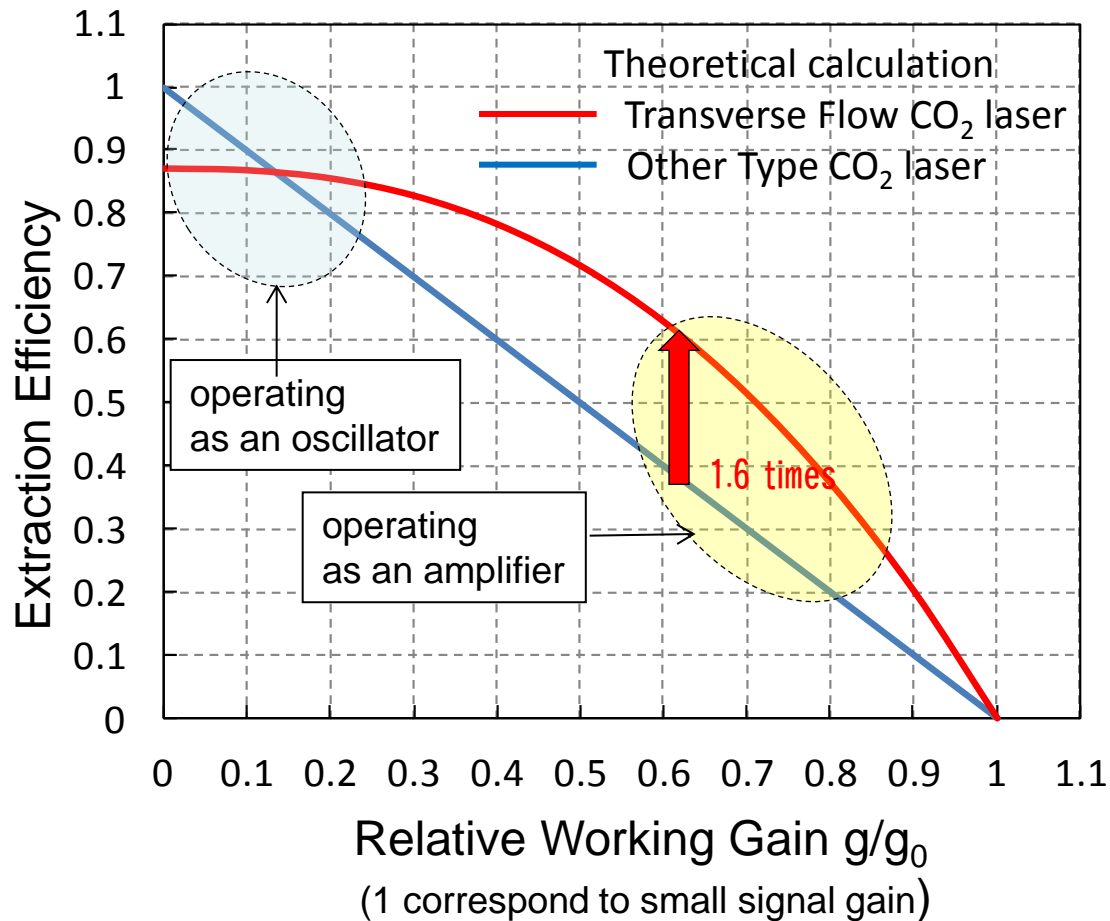


- Output pulse duration: 23 ns
- Expected pulse stretch

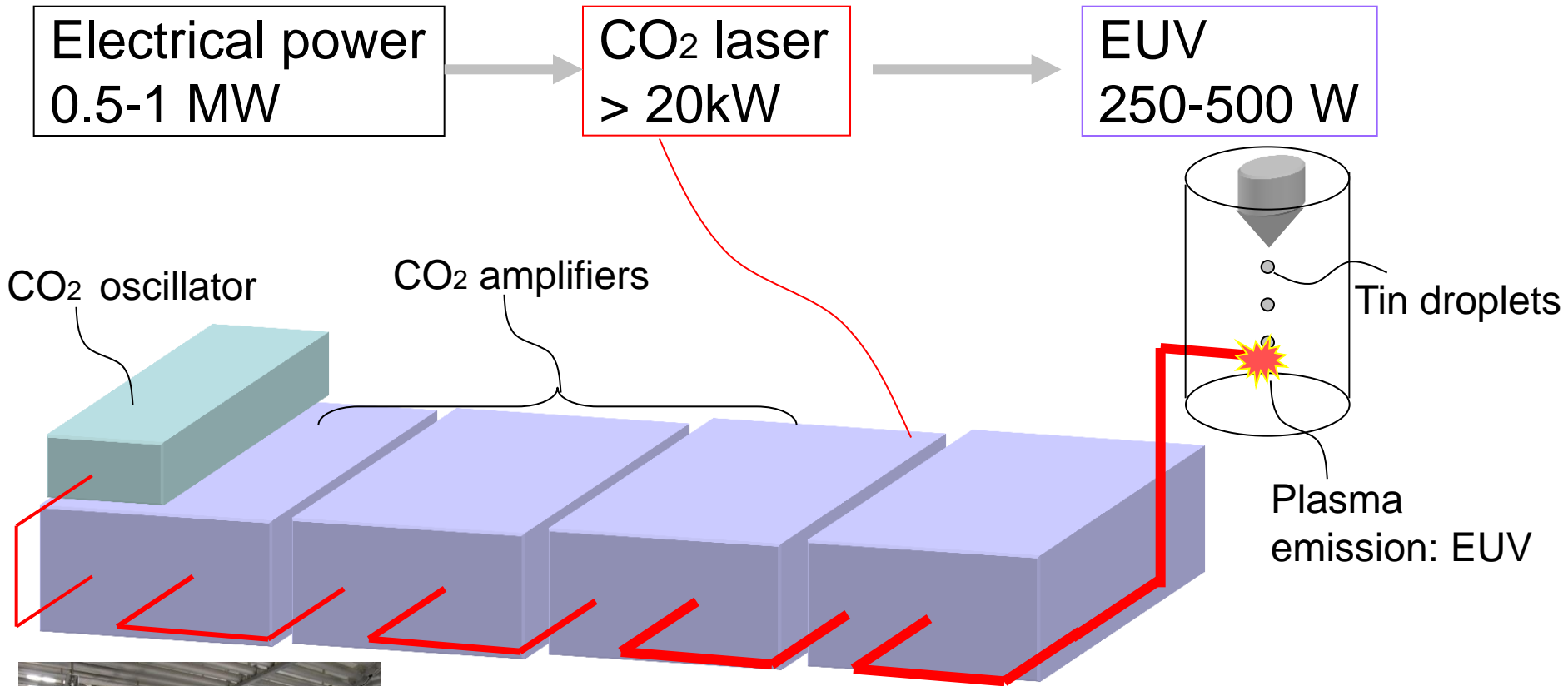
### Experimental results summary

1. CO<sub>2</sub> laser power of 21 kW was achieved.
2. Higher power (approximately, 1.6times) was achieved compared with axial-flow CO<sub>2</sub> lasers at the same electrical input of 400kW.
3. Electrical-to-optical efficiency was 5.3%

## Theoretical calculations



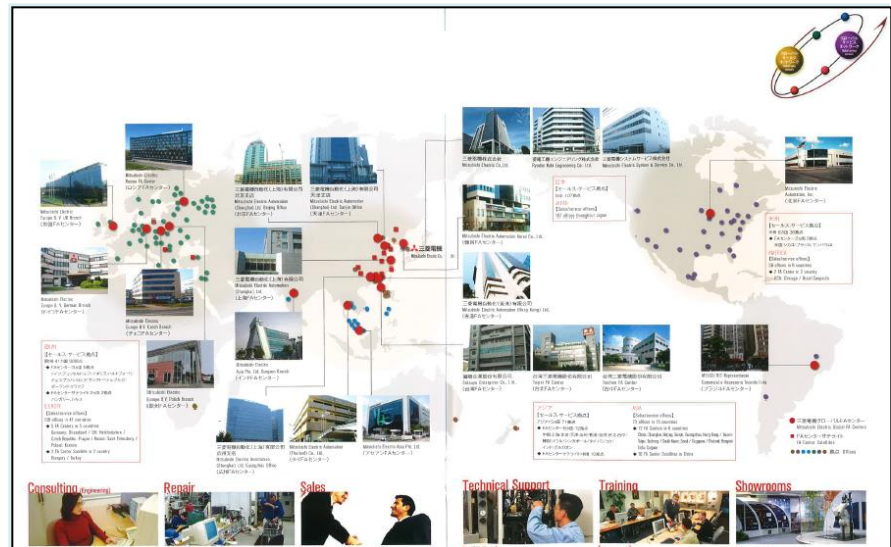
## EUV generation by using transverse-gas-flow CO<sub>2</sub> lasers



# IV. Future prospects (2/2)

By applying our solution: transverse-gas-flow CO<sub>2</sub> lasers,

1. Driver power saturation problems could be solved.
2. Physical stability of EUV powers could be improved.
3. Reliable supply could be guaranteed backed up healthy growing material processing markets.





- The experiments were performed by research members at the advanced technology R&D center, Mitsubishi Electric corp. with valuable supports by Gigaphoton Inc.



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Thank you very much for your attention.

Thank you again for your invitation to this workshop.

